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(54) VERTICAL CAVITY SURFACE EMITTING LASER AND ATOMIC OSCILLATOR

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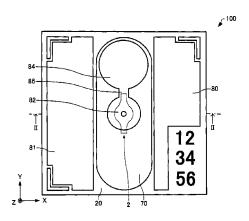
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(57)ABSTRACT

A vertical cavity surface emitting laser includes: a substrate; a first mirror layer which is provided over the substrate; an active layer which is provided over the first mirror layer; a second mirror layer which is provided over the active layer; a first electrode and a second electrode which are electrically connected to the first mirror layer and are separated from each other; and a third electrode which is electrically connected to the second mirror layer, wherein the first mirror layer, the active layer, and the second mirror layer configure a laminated body, the laminated body includes a resonance portion which resonates light generated in the active layer, in a plan view, an insulation layer surrounding the laminated body is provided, and in the plan view, the insulation layer is provided between the first electrode and the second electrode.

4 Claims, 6 Drawing Sheets



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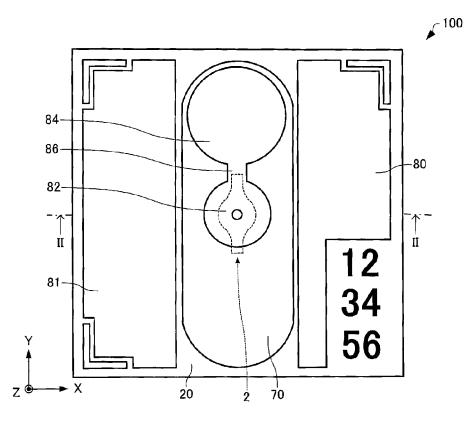


FIG. 1

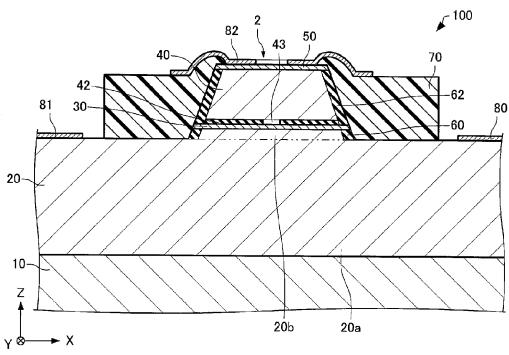


FIG. 2

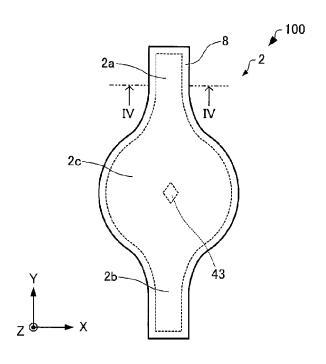


FIG. 3

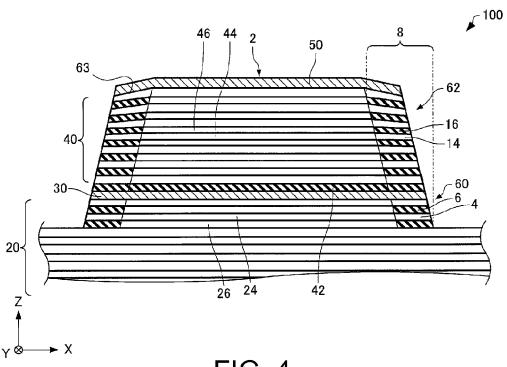


FIG. 4

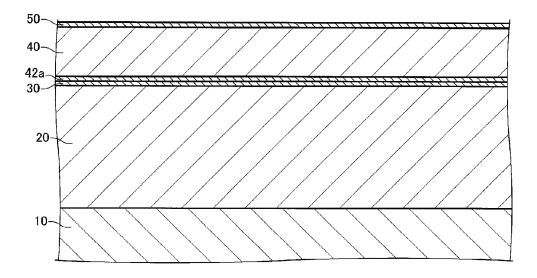


FIG. 5

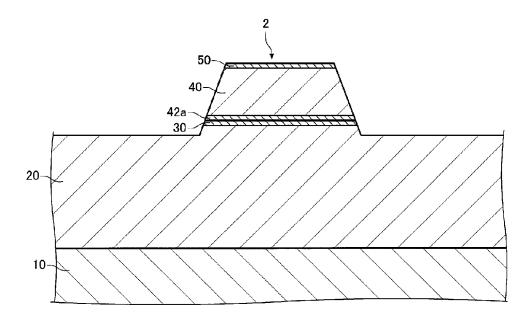


FIG. 6

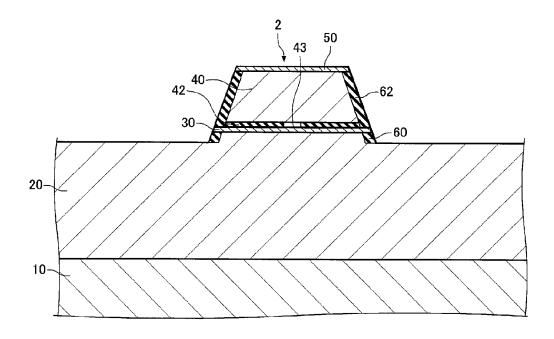


FIG. 7

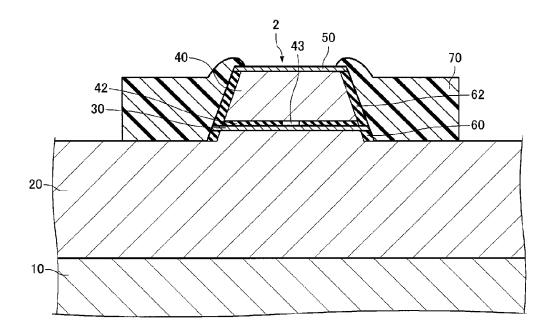


FIG. 8

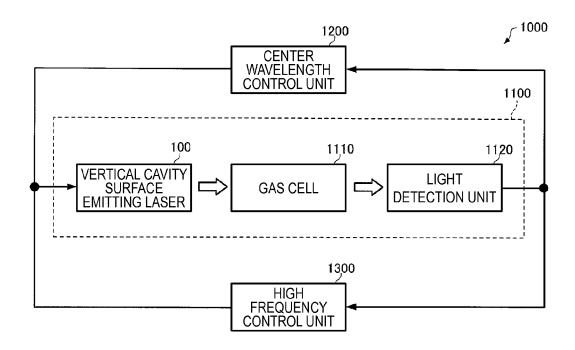


FIG. 9

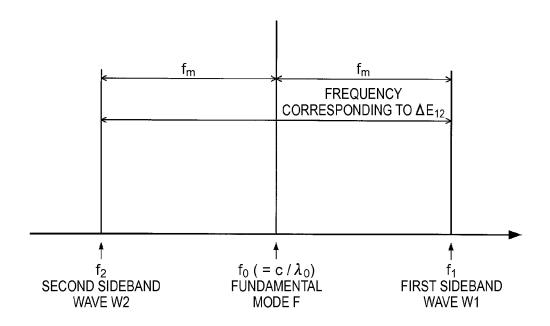


FIG.10

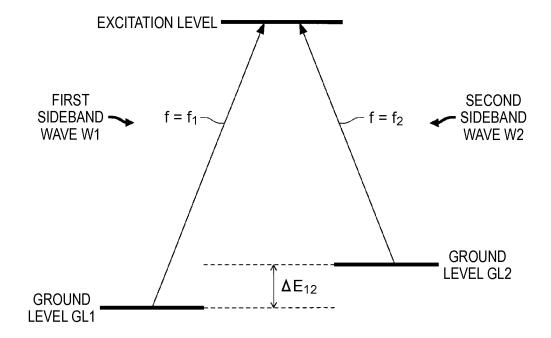


FIG.11

VERTICAL CAVITY SURFACE EMITTING LASER AND ATOMIC OSCILLATOR

BACKGROUND

1. Technical Field

The present invention relates to a vertical cavity surface emitting laser and an atomic oscillator.

2. Related Art

The vertical cavity surface emitting laser (VCSEL) is, for 10 example, used as a light source of the atomic oscillator using coherent population trapping (CPT) which is one of the quantum interference effects.

JP-A-2007-165501, for example, discloses a vertical cavity surface emitting laser including: a columnar (vertical reso-15 nator) which is configured with a portion of a first mirror, an active layer, and a second mirror; an electrode which is provided on the first mirror; and an electrode which is provided on the second mirror.

However, in the vertical cavity surface emitting laser dis- 20 closed in JP-A-2007-165501, the electrode which is provided on the first mirror is only disposed on one side of the vertical resonator, and thus electric field distribution may be asymmetric with respect to the vertical resonator. When the electric field distribution is asymmetric with respect to the vertical 25 resonator, intensity of laser light emitted from the vertical resonator, for example, may be asymmetric.

SUMMARY

An advantage of some aspects of the invention is to provide a vertical cavity surface emitting laser which can improve symmetry of electric field distribution with respect to a resonance portion. In addition, another advantage of some aspects of the invention is to provide an atomic oscillator including 35 the vertical cavity surface emitting laser.

An aspect of the invention is directed to a vertical cavity surface emitting laser including: a substrate; a first mirror layer which is provided over the substrate; an active layer which is provided over the first mirror layer; a second mirror 40 layer which is provided over the active layer; a first electrode and a second electrode which are electrically connected to the first mirror layer and are separated from each other; and a third electrode which is electrically connected to the second mirror layer, in which the first mirror layer, the active layer, 45 vertical cavity surface emitting laser according to the embodiand the second mirror layer configure a laminated body, the laminated body includes a resonance portion which resonates light generated in the active layer, in a plan view, an insulation layer surrounding the laminated body is provided, and in the plan view, the insulation layer is provided between the first 50 electrode and the second electrode.

According to the vertical cavity surface emitting laser, since the insulation layer surrounding the laminated body is disposed between the first electrode and the second electrode, in a plan view, it is possible to improve symmetry of electric 55 field distribution with respect to the resonance portion, for example, compared to a case where the electrode is only formed on one side of the insulation layer.

In the description according to the invention, for example, when a term "over" is used in a sentence such as "to form a 60 specific element (hereinafter, referred to as a "B") over another specific element (hereinafter, referred to as an "A")" the term "over" is used to include a case of forming the B directly on the A and a case of forming the B on the A with another element interposed therebetween.

In the description according to the invention, for example, a phrase "electrical connection" is used with "a specific mem2

ber (hereinafter, referred to as a "B member") which is "electrically connected" to another specific member (hereinafter, referred to as an "A member")". In the description according to the invention, in such an example, the phrase "electrical connection" is used to include a case where the A member and the B member directly come in contact with each other and are electrically connected, and a case where the A member and the B member are electrically connected with another member interposed therebetween.

In the vertical cavity surface emitting laser according to the aspect of the invention, in the plan view, the resonance portion may be provided between the first electrode and the second

According to the vertical cavity surface emitting laser, it is possible to improve the symmetry of the electric field distribution with respect to the resonance portion.

In the vertical cavity surface emitting laser according to the aspect of the invention, the first mirror layer may include a first portion which is provided over the substrate, and a second portion which is provided over the first portion and configures a portion of the laminated body, the first electrode and the second electrode may be provided on the first portion, and the third electrode may be provided on the laminated body.

According to the vertical cavity surface emitting laser, it is possible to improve the symmetry of the electric field distribution with respect to the resonance portion.

Another aspect of the invention is directed to an atomic oscillator including the vertical cavity surface emitting laser according to the aspect of the invention.

In such an atomic oscillator, it is possible to include a vertical cavity surface emitting laser which can improve the symmetry of the electric field distribution with respect to the resonance portion.

BRIEF DESCRIPTION OF THE DRAWINGS

The invention will be described with reference to the accompanying drawings, wherein like numbers reference like elements.

FIG. 1 is a plan view schematically showing a vertical cavity surface emitting laser according to the embodiment.

FIG. 2 is a cross-sectional view schematically showing a ment.

FIG. 3 is a plan view schematically showing a vertical cavity surface emitting laser according to the embodiment.

FIG. 4 is a cross-sectional view schematically showing a vertical cavity surface emitting laser according to the embodi-

FIG. 5 is a cross-sectional view schematically showing a manufacturing step of a vertical cavity surface emitting laser according to the embodiment.

FIG. 6 is a cross-sectional view schematically showing a manufacturing step of a vertical cavity surface emitting laser according to the embodiment.

FIG. 7 is a cross-sectional view schematically showing a manufacturing step of a vertical cavity surface emitting laser according to the embodiment.

FIG. 8 is a cross-sectional view schematically showing a manufacturing step of a vertical cavity surface emitting laser according to the embodiment.

FIG. 9 is a functional block diagram of an atomic oscillator according to the embodiment.

FIG. 10 is a view showing frequency spectra of resonant

FIG. 11 is a view showing a relationship between Λ -shaped three level models of an alkaline metal atom, a first sideband wave, and a second sideband wave.

DESCRIPTION OF EXEMPLARY EMBODIMENTS

Hereinafter, preferred embodiments of the invention will be described in detail with reference to the drawings. The embodiments described below are not intended to unduly limit the contents of the invention disclosed in the aspects. All of the configurations described below are not limited to the essential constituent elements of the invention.

1. Vertical Cavity Surface Emitting Laser

First, a vertical cavity surface emitting laser according to 15 the embodiment will be described with reference to the drawings. FIG. 1 is a plan view schematically showing a vertical cavity surface emitting laser 100 according to the embodiment. FIG. 2 is a cross-sectional view which is taken along line II-II of FIG. 1 and schematically shows the vertical cavity surface emitting laser 100 according to the embodiment. FIG. 3 is a plan view schematically showing the vertical cavity surface emitting laser 100 according to the embodiment. FIG. 4 is a cross-sectional view which is taken along line IV-IV of FIG. 3 and schematically shows the vertical cavity surface emitting laser 100 according to the embodiment.

For the sake of convenience, FIG. 2 shows a simplified laminated body 2. In FIG. 3, members other than the laminated body 2 of the vertical cavity surface emitting laser 100 are omitted. FIGS. 1 to 4 show an X axis, a Y axis, and a Z axis 30 as three axes orthogonal to each other.

As shown in FIGS. 1 to 4, the vertical cavity surface emitting laser 100 includes a substrate 10, a first mirror layer 20, an active layer 30, a second mirror layer 40, a current constriction layer 42, a contact layer 50, first areas 60, second 35 areas 62, a resin layer (insulation layer) 70, a first electrode 80, a second electrodes 81, and a third electrode 82.

The substrate 10 is, for example, a first conductive (for example, n-type) GaAs substrate.

The first mirror layer **20** is formed on the substrate **10**. The 40 first mirror layer **20** is a first conductive semiconductor layer. As shown in FIG. **4**, the first mirror layer **20** is a distribution Bragg reflection (DBR) type mirror in which high refractive index layers **24** and low refractive index layers **26** are laminated onto each other. The high refractive index layer **24** is, 45 for example, an n-type Al_{0.12}Ga_{0.88}As layer on which silicon is doped. The low refractive index layer **26** is, for example, an n-type Al_{0.9}Ga_{0.1}As layer on which silicon is doped. The number (number of pairs) of laminated high refractive index layers **24** and low refractive index layers **26** is, for example, 50 pairs to 50 pairs, specifically, 40.5 pairs.

The active layer 30 is provided on the first mirror layer 20. The active layer 30, for example, has a multiple quantum well (MQW) structure in which three layers having a quantum well structure configured with an i-type $In_{0.06}Ga_{0.94}As$ layer 55 and an i-type $Al_{0.3}Ga_{0.7}As$ layer are overlapped.

The second mirror layer 40 is formed on the active layer 30. The second mirror layer 40 is a second conductive (for example, p-type) semiconductor layer. The second mirror layer 40 is a distribution Bragg reflection (DBR) type mirror 60 in which high refractive index layers 44 and low refractive index layers 46 are laminated onto each other. The high refractive index layer 44 is, for example, a p-type $Al_{0.12}Ga_{0.88}As$ layer on which carbon is doped. The low refractive index layer 46 is, for example, a p-type 65 $Al_{0.9}Ga_{0.1}As$ layer on which carbon is doped. The number (number of pairs) of laminated high refractive index layers 44

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and low refractive index layers **46** is, for example, 3 pairs to 40 pairs, specifically, 20 pairs.

The second mirror layer 40, the active layer 30, and the first mirror layer 20 configure a vertical resonator-type pin diode. When a forward voltage of the pin diode is applied between the electrodes 80 and 81, and the electrode 82, recombination between electrons and positive holes occurs in the active layer 30, and the light emitting occurs. The light generated in the active layer 30 reciprocates between the first mirror layer 20 and the second mirror layer 40 (multiple reflection), the induced emission occurs at that time, and the intensity is amplified. When an optical gain exceeds an optical loss, laser oscillation occurs, and the laser light is emitted in a vertical direction (a lamination direction of the first mirror layer 20 and the active layer 30) from the upper surface of the contact layer 50.

The current constriction layer 42 is provided between the first mirror layer 20 and the second mirror layer 40. The current constriction layer 42 can also be provided in the first mirror layer 20 or the second mirror layer 40. In this case as well, the current constriction layer 42 is assumed to be provided between the first mirror layer 20 and the second mirror layer 40. In the example shown in the drawing, the current constriction layer 42 is provided on the active layer 30. The current constriction layer 42 is an insulation layer in which an opening 43 is formed. The current constriction layer 42 can prevent spreading of the current injected to a vertical resonator by the electrodes 80, 81, and in a planar direction (direction orthogonal to the lamination direction of the first mirror layer 20 and the active layer 30).

The contact layer **50** is provided on the second mirror layer **40**. The contact layer **50** is a second conductive semiconductor layer. Specifically, the contact layer **50** is a p-type GaAs layer on which carbon is doped.

As shown in FIG. 4, the first areas 60 are provided on lateral portions of the first mirror layer 20 configuring the laminated body 2. The first areas 60 include a plurality of oxide layers 6 which are provided to be connected to the first mirror layer 20 (in the example shown in the drawing, a part of the first mirror layer 20). Specifically, first areas 60 are configured with the oxide layers 6 obtained by oxidizing layers connected to the low refractive index layers 26 (for example, $Al_{0.9}Ga_{0.1}As$ layers) configuring the first mirror layer 20, and layers 4 connected to the high refractive index layers 24 (for example, $Al_{0.12}Ga_{0.88}As$ layers) configuring the first mirror layer 20 which are laminated on each other.

The second areas **62** are provided on lateral portions of the second mirror layer **40** configuring the laminated body **2**. The second areas **62** include a plurality of oxide layers **16** which are provided to be connected to the second mirror layer **40**. Specifically, the second areas **62** are configured with the oxide layers **16** obtained by oxidizing layers connected to the low refractive index layers **46** (for example, $Al_{0.9}Ga_{0.1}As$ layers) configuring the second mirror layer **40**, and layers **14** connected to the high refractive index layers **44** (for example, $Al_{0.12}Ga_{0.88}As$ layers) configuring the second mirror layer **40** which are laminated on each other. In a plan view (when seen from the lamination direction of the first mirror layer **20** and the active layer **30**), oxide areas **8** are configured by the first areas **60** and the second areas **62**.

The first mirror layer 20, the active layer 30, the second mirror layer 40, the current constriction layer 42, the contact layer 50, the first areas 60, and the second areas 62 configure the laminated body 2. In the example shown in FIGS. 1 and 2, the laminated body 2 is surrounded with the resin layer 70.

In the example shown in FIG. 3, in a plan view, a length of the laminated body 2 in a Y axis direction is greater than a

length of the laminated body 2 in an X axis direction. That is, a longitudinal direction of the laminated body 2 is the Y axis direction. In a plan view, the laminated body 2 is, for example, symmetrical about a virtual straight line which passes through the center of the laminated body 2 and is parallel to 5 the X axis. In a plan view, the laminated body 2 is, for example, symmetrical about a virtual straight line which passes through the center of the laminated body 2 and is parallel to the Y axis.

In a plan view as shown in FIG. 3, the laminated body 2 $\,^{10}$ includes a first distortion imparting portion (first portion) 2a, a second distortion imparting portion (second portion) 2b, and a resonance portion (third portion) 2c.

In a plan view, the first distortion imparting portion 2a and the second distortion imparting portion 2b face each other in the Y axis direction with the resonance portion 2c interposed therebetween. In a plan view, the first distortion imparting portion 2a is protruded from the resonance portion 2c in the positive Y axis direction. In a plan view, the second distortion imparting portion 2b is protruded from the resonance portion 2c in the negative Y axis direction. The first distortion imparting portion 2a and the second distortion imparting portion 2b are provided to be integrated with the resonance portion 2c.

The first distortion imparting portion 2a and the second distortion imparting portion 2b impart distortion to the active 25 layer 30 and polarize light generated in the active layer 30. Herein, to polarize the light is to set a vibration direction of an electric field of the light to be constant. The semiconductor layers (the first mirror layer 20, the active layer 30, the second mirror layer 40, the current constriction layer 42, the contact 30 layer 50, the first areas 60, and the second areas 62) configuring the first distortion imparting portion 2a and the second distortion imparting portion 2b are a generation source which generates distortion to be imparted to the active layer 30. Since the first distortion imparting portion 2a and the second 35 distortion imparting portion 2b include the first areas 60 including the plurality of oxide layers 6 and the second areas 62 including the plurality of oxide layers 16, it is possible to impart a large amount of distortion to the active layer 30.

The resonance portion 2c is provided between the first 40 distortion imparting portion 2a and the second distortion imparting portion 2b. A length of the resonance portion 2c in the X axis direction is greater than a length of the first distortion imparting portion 2a in the X axis direction or a length of the second distortion imparting portion 2b in the X axis direction. A planar shape of the resonance portion 2c (shape when seen from the lamination direction of the first mirror layer 2b and the active layer 3b) is, for example, a circle.

The resonance portion 2c resonates light generated in the active layer 30. That is, the vertical resonator is formed in the 50 resonance portion 2c.

The resin layer 70 is provided at least on side surfaces of the laminated body 2. In the example shown in FIG. 1, the resin layer 70 covers the first distortion imparting portion 2a and the second distortion imparting portion 2b.

That is, the resin layer 70 is provided on the side surface of the first distortion imparting portion 2a, the upper surface of the first distortion imparting portion 2a, the side surface of the second distortion imparting portion 2b, and the upper surface of the second distortion imparting portion 2b. The resin layer 60 may completely cover the first distortion imparting portion 2a and the second distortion imparting portion 2a or may cover some of the first distortion imparting portion 2a and the second distortion imparting portion 2b. The material of the resin layer 70 is, for example, polyimide. In the embodiment, 65 the resin layer 70 for applying the distortion to the distortion imparting portions 2a and 2b is used, but since a configuration

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corresponding to the resin layer 70 is only necessary to have a function of insulating, the resin may not be used, as long as it is an insulation material.

In the example shown in FIG. 3, in a plan view, a length of the resin layer 70 in the Y axis direction is greater than a length of the resin layer 70 in the X axis direction. That is, a longitudinal direction of the resin layer 70 is the Y axis direction. The longitudinal direction of the resin layer 70 and the longitudinal direction of the laminated body 2 coincide with each other.

The first electrode 80 and the second electrode 80 and the second electrode 80 and the second electrode 81 form ohmic contact with the first mirror layer 20. The first electrode 80 and the second electrode 81 are electrically connected to the first mirror layer 20. As the first electrode 80 and the second electrode 81, an electrode in which a Cr layer, an AuGe layer, an Ni layer, and an Au layer are laminated in this order from the first mirror layer 20 side is used, for example. The first electrode 80 and the second electrode 81 are the electrodes for injecting the current to the active layer 30.

The third electrodes 82 are provided on the contact layer 50 (on the laminated body 2). The third electrodes 82 form ohmic contact with the contact layer 50. In the example shown in the drawing, the third electrodes 82 are also formed on the resin layer 70. The third electrodes 82 are electrically connected to the second mirror layer 40 through the contact layer 50. As the third electrodes 82, an electrode in which a Cr layer, a Pt layer, a Ti layer, a Pt layer, and an Au layer are laminated in this order from the contact layer 50 side is used, for example. The third electrodes 82 are the other electrodes for injecting the current to the active layer 30.

The third electrodes 82 are electrically connected to a pad 84. In the example shown in the drawing, the third electrodes 82 are electrically connected to the pad 84 through a lead-out wiring 86. The pad 84 is provided on the resin layer 70. The material of the pad 84 and the lead-out wiring 86 is, for example, the same as the material of the third electrodes 82.

Herein, the first electrode 80 and the second electrode 81 will be described in detail.

The first electrode **80** and the second electrode **81** are provided to be separated from each other. That is, the first electrode **80** and the second electrode **81** are provided to be separated with a gap therebetween. In a plan view, the resin layer **70** is provided between the first electrode **80** and the second electrode **81**. In the example shown in the drawing, the first electrode **80** is provided on one side (positive X axis direction side) of the resin layer **70** in a plan view, and the second electrode **81** is provided on the other side (negative X axis direction side) of the resin layer **70** in a plan view. As described above, in the vertical cavity surface emitting laser **100**, electrodes electrically connected to the first mirror layer **20** are divided into the first electrode **80** and the second electrode **81** and are provided on both sides of the resin layer **70**, respectively.

In a plan view, a length (for example, the greatest length) of the first electrode 80 in the Y axis direction is greater than a length (for example, the greatest length) of the first electrode 80 in the X axis direction. That is, the first electrode 80 has a shape having a longitudinal direction in the Y axis direction. In addition, in a plan view, a length (for example, the greatest length) of the second electrode 81 in the Y axis direction is greater than a length (for example, the greatest length) of the second electrode 81 in the X axis direction. That is, the second electrode 81 has a shape having a longitudinal direction in the Y axis direction. The longitudinal direction of the first electrode 80 and the longitudinal direction of the second electrode

81 are the same direction as the longitudinal direction of the resin layer **70**. The greatest length of the first electrode **80** in the Y axis direction is equivalent to the greatest length of the second electrode **81** in the Y axis direction.

In a plan view, the resin layer 70 is provided so as to 5 surround the resonance portion 2c. In a plan view, the resonance portion 2c is provided between the first electrode 80 and the second electrode 81. For example, in a plan view, a distance (shortest distance) between the resonance portion 2c and the first electrode 80 is equivalent to a distance (shortest distance) between the resonance portion 2c and the second electrode 81.

As shown in FIG. 2, the first mirror layer 20 includes a first portion 20a which is provided on the substrate 10, and a second portion 20b which is provided on the first portion 20a and configures a part of the laminated body 2. The first electrode 80 and the second electrode 81 are provided on the first portion 20a of the first mirror layer 20. As described above, the third electrode 82 is provided on the laminated body 2. As described above, the electrodes 80, 81, and 82 are provided on the upper surface side (positive Z axis direction side) of the substrate 10.

In the above description, the AlGaAs vertical cavity surface emitting laser has been described, but GaInP, ZnSSe, InGaN, AlGaN, InGaAs, GaInNAs, or GaAsSb semiconductor materials may be used according to the oscillation wavelength, for the vertical cavity surface emitting laser according to the invention.

The vertical cavity surface emitting laser 100, for example, has the following characteristics.

In the vertical cavity surface emitting laser 100, in a plan view, the resin layer 70 is provided so as to surround the laminated body 2 and the resin layer 70 is provided between the first electrode 80 and the second electrode 81. Accordingly, it is possible to improve symmetry of electric field 35 distribution with respect to the resonance portion 2c, for example, compared to a case where the electrode is only formed on one side of the resin layer 70 (compared to a case where the first electrode 80 is only provided, for example). In the vertical cavity surface emitting laser 100, since the first 40 electrode 80 and the second electrode 81 are separated from each other, the connected portion of the first electrode 80 and the second electrode 81 is not necessary and it is possible to realize miniaturization, for example, compared to a case where the first electrode 80 and the second electrode 81 are 45 connected to each other.

In the vertical cavity surface emitting laser 100, in a plan view, the resonance portion 2c is provided between the first electrode 80 and the second electrode 81. Accordingly, it is possible to improve the symmetry of the electric field distribution with respect to the resonance portion 2c, for example, compared to a case where the electrode is only formed on one side of the resin layer 70.

In the vertical cavity surface emitting laser 100, the first electrode 80 and the second electrode 81 are provided on the 55 first portion 20a of the first mirror layer 20 and the third electrode 82 is provided on the laminated body 2. Accordingly, it is possible to obtain a one-sided electrode structure, for example.

2. Manufacturing Method of Vertical Cavity Surface Emitting 60 Laser

Next, a manufacturing method of the vertical cavity surface emitting laser according to the embodiment will be described with reference to the drawings. FIGS. 5 to 8 are cross-sectional views schematically showing manufacturing steps of 65 the vertical cavity surface emitting laser 100 according to the embodiment, and correspond to FIG. 2.

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As shown in FIG. 5, the first mirror layer 20, the active layer 30, the layer to be oxidized 42a which is to be the oxidized current constriction layer 42, the second mirror layer 40, and the contact layer 50 are epitaxially grown in this order, on the substrate 10. As an epitaxial growth method, a metal organic chemical vapor deposition (MOCVD) method or a molecular beam epitaxy (MBE) method is used, for example.

As shown in FIG. 6, the contact layer 50, the second mirror layer 40, the layer to be oxidized 42a, the active layer 30, and first mirror layer 20 are patterned to form the laminated body 2. The patterning is performed by photolithography or etching, for example.

As shown in FIG. 7, the layer to be oxidized 42a is oxidized to form the current constriction layer 42. The layer to be oxidized 42a is, for example, an $Al_xGa_{1-x}As$ ($x \ge 0.95$) layer. The substrate 10 on which the laminated body 2 is formed is put in a steam atmosphere at approximately 400° C., to oxidize the $Al_xGa_{1-x}As$ ($x \ge 0.95$) layer from the lateral side, and accordingly the current constriction layer 42 is formed.

In the manufacturing method of the vertical cavity surface emitting laser 100, in the oxidization step, a layer configuring the first mirror layer 20 is oxidized from the lateral side to form the first area 60. A layer configuring the second mirror layer 40 is oxidized from the lateral side to form the second area 62. Specifically, due to the steam atmosphere at approximately 400° C., arsenic in the Al_{0.9}Ga_{0.1}As layer configuring the mirror layers 20 and 40 is substituted with oxygen, and the areas 60 and 62 are formed. The areas 60 and 62, for example, contract when returning the temperature from the high temperature of approximately 400° C. to the room temperature, and the upper surface 63 of the second area 62 is inclined to the substrate 10 side (see FIG. 4). The first distortion imparting portion 2a and the second distortion imparting portion 2b can apply distortion (stress) caused by the contraction of the areas 60 and 62 to the active layer 30.

As shown in FIG. **8**, the resin layer **70** is formed so as to surround the laminated body **2**. The resin layer **70** is formed, for example, by forming a layer formed of a polyimide resin on the upper surface of the first mirror layer **20** and the entire surface of the laminated body **2** using a spin coating method and patterning the layer. The patterning is performed by photolithography or etching, for example. Next, the resin layer **70** is hardened by performing a heating process (curing). The resin layer **70** contracts due to the heating process. In addition, the resin layer **70** contracts when returning the temperature in the heating step to a room temperature.

As shown in FIG. 2, the third electrode 82 is formed on the contact layer 50 and the resin layer 70, and the first electrode 80 and the second electrode 81 are formed on the first mirror layer 20. In a plan view, the first electrode 80 is formed on one side of the resin layer 70 and the second electrode 81 is formed on the other side of the resin layer 70, in a plan view. The electrodes 80, 81, and 82 are, for example, formed by a combination of a vacuum vapor deposition method and a lift-off method. The order of forming the electrodes 80, 81 and 82 is not particularly limited. In the step of forming the third electrode 82, the pad 84 and the lead-out wiring 86 (see FIG. 1) may be formed. A chip number provided in a chip number writing area 90 may be formed in a step of forming the electrodes 80 and 81, or may be formed in a step of forming the third electrode 82.

It is possible to manufacture the vertical cavity surface emitting laser 100 with the steps described above.

3. Atomic Oscillator

Next, an atomic oscillator according to the embodiment will be described with reference to the drawings. FIG. 9 is a functional block diagram of an atomic oscillator 1000 according to the embodiment.

As shown in FIG. 9, the atomic oscillator 1000 is configured to include an optical module 1100, a center wavelength control unit 1200, and a high frequency control unit 1300.

The optical module 1100 includes the vertical cavity surface emitting laser according to the invention (in the example 10 shown in the drawing, the vertical cavity surface emitting laser 100), a gas cell 1110, and a light detection unit 1120.

FIG. 10 is a view showing frequency spectra of light emitted by the vertical cavity surface emitting laser 100. FIG. 11 is a view showing a relationship between Λ -shaped three level 15 models of an alkaline metal atom, a first sideband wave W1, and a second sideband wave W2. The light emitted from the vertical cavity surface emitting laser 100 includes a fundamental mode F including a center frequency f_0 (=c/ λ_0 : c represents velocity of light and λ_0 represents a center wave- 20 length of laser light), the first sideband wave W1 including a frequency f₁ in an upstream sideband with respect to the center frequency fo, and the second sideband wave W2 including a frequency f2 in an downstream sideband with respect to the center frequency f_0 , shown in FIG. 10. The 25 frequency f_1 of the first sideband wave W1 satisfies $f_1 = f_0 + f_m$, and the frequency f₂ of the second sideband wave W2 satisfies $f_2 = f_0 - f_m$.

As shown in FIG. 11, a difference in frequencies between the frequency f_1 of the first sideband wave W1 and the frequency f_2 of the second sideband wave W2 coincides with a frequency corresponding to a difference in energy ΔE_{12} between a ground level GL1 and a ground level GL2 of the alkaline metal atom. Accordingly, the alkaline metal atom causes an EIT phenomenon to occur due to the first sideband wave W1 including the frequency f_1 and the second sideband wave W2 including the frequency f_2 .

In the gas cell 1110, a gaseous alkaline metal atom (sodium atom, rubidium atom, cesium atom, and the like) is sealed in a container. When two light waves including the frequency 40 (wavelength) corresponding to the difference in energy between two ground levels of the alkaline metal atom are emitted to the gas cell 1110, the alkaline metal atom causes the EIT phenomenon to occur. For example, if the alkaline metal atom is a sodium atom, the frequency corresponding to 45 the difference in energy between the ground level GL1 and the ground level GL2 in a D1 line is 9.19263 . . . GHz. Accordingly, when two light waves including the difference in frequency of 9.19263 . . . GHz are emitted, the EIT phenomenon occurs.

The light detection unit 1120 detects the intensity of the light penetrating the alkaline metal atom sealed in the gas cell 1110. The light detection unit 1120 outputs a detection signal according to the amount of the light penetrating the alkaline metal atom. As the light detection unit 1120, a photodiode is 55 used, for example.

The center wavelength control unit 1200 generates driving current having a magnitude corresponding to the detection signal output by the light detection unit 1120, supplies the driving current to the vertical cavity surface emitting laser 60 100, and controls the center wavelength λ_0 of the light emitted by the vertical cavity surface emitting laser 100. The center wavelength λ_0 of the laser light emitted by the vertical cavity surface emitting laser 100 is minutely adjusted and stabilized, by a feedback loop passing through the vertical cavity surface emitting laser 100, the gas cell 1110, the light detection unit 1120, and the center wavelength control unit 1200.

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The high frequency control unit 1300 controls so that the difference in wavelengths (frequencies) between the first sideband wave W1 and the second sideband wave W2 is equivalent to the frequency corresponding to the difference in energy between two ground levels of the alkaline metal atom sealed in the gas cell 1110, based on the detection result output by the light detection unit 1120. The high frequency control unit 1300 generates a modulation signal including a modulation frequency f_m (see FIG. 10) according to the detection result output by the light detection unit 1120.

Feedback control is performed so that the difference in frequencies between the first sideband wave W1 and the second sideband wave W2 is extremely accurately equivalent to the frequency corresponding to the difference in energy between two ground levels of the alkaline metal atom, by a feedback loop passing through the vertical cavity surface emitting laser 100, the gas cell 1110, the light detection unit 1120, and the high frequency control unit 1300. As a result, the modulation frequency f_m becomes an extremely stabilized frequency, and therefore, the modulation signal can be set as an output signal (clock output) of the atomic oscillator 1000.

Next, the operations of the atomic oscillator 1000 will be described with reference to FIGS. 9 to 11.

The laser light emitted from the vertical cavity surface emitting laser 100 is incident to the gas cell 1110. The light emitted from the vertical cavity surface emitting laser 100 includes two light waves (the first sideband wave W1 and the second sideband wave W2) including the frequency (wavelength) corresponding to the difference in energy between two ground levels of the alkaline metal atom, and the alkaline metal atom causes the EIT phenomenon to occur. The intensity of the light penetrating the gas cell 1110 is detected by the light detection unit 1120.

The center wavelength control unit **1200** and the high frequency control unit **1300** perform the feedback control so that the difference in frequencies between the first sideband wave W1 and the second sideband wave W2 extremely accurately coincides with the frequency corresponding to the difference in energy between two ground levels of the alkaline metal atom. In the atomic oscillator **1000**, a rapid change in a light absorbing behavior when the difference in frequencies f_1 - f_2 between the first sideband wave W1 and the second sideband wave W2 is deviated from the frequency corresponding to the difference in energy ΔE_{12} between the ground level GL1 and the ground level GL2, is detected and controlled using the EIT phenomenon, and therefore it is possible to obtain an oscillator with high accuracy.

The invention has configurations substantially same as the configurations described in the embodiments (for example, configurations with the same function, method, and effects, or configurations with the same object and effect). The invention includes a configuration in which non-essential parts of the configurations described in the embodiments are replaced. The invention includes a configuration having the same operation effect as the configurations described in the embodiments or a configuration which can achieve the same object. The invention includes a configuration obtained by adding a well-known technology to the configurations described in the embodiments.

The entire disclosure of Japanese Patent Application No. 2013-263467, filed Dec. 20, 2013 is expressly incorporated by reference herein.

What is claimed is:

- 1. A vertical cavity surface emitting laser comprising: a substrate:
- a first mirror layer which is provided over the substrate; an active layer which is provided over the first mirror layer;

- a second mirror layer which is provided over the active layer;
- a first electrode and a second electrode which are electrically connected to the first mirror layer and are separated from each other; and
- a third electrode which is electrically connected to the second mirror layer,
- wherein the first mirror layer, the active layer, and the second mirror layer configure a laminated body,
- the laminated body includes a resonance portion which 10 resonates light generated in the active layer,
- in a plan view, an insulation layer surrounding the laminated body is provided, and
- in the plan view, the insulation layer is provided between the first electrode and the second electrode,
- the first mirror layer includes a first portion which is provided over the substrate, and a second portion which is provided over the first portion and configures a portion of the laminated body,
- the first electrode and the second electrode are provided on 20 the first portion, and
- the third electrode is provided on the laminated body.
- 2. The vertical cavity surface emitting laser according to claim 1.
 - wherein, in the plan view, the resonance portion is provided 25 between the first electrode and the second electrode.
 - 3. An atomic oscillator comprising:
 - the vertical cavity surface emitting laser according to claim
 - 4. An atomic oscillator comprising:
 - the vertical cavity surface emitting laser according to claim

 2.

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